

AMENDMENTS TO THE CLAIMS:

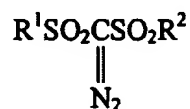
Please cancel claims 28-31 without prejudice and add new claims 32-35.

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

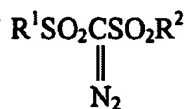
Claims 1-6 (Canceled).

Claim 7 (Previously Presented): A diazodisulfone compound of the formula:



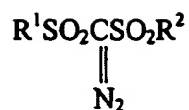
wherein R¹ is a branched alkyl group having 3 to 8 carbon atoms; and R² is a cyclic alkyl group having 3 to 8 carbon atoms.

Claim 8 (Previously Presented): A diazodisulfone compound of the formula:



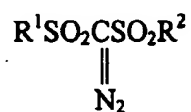
wherein R¹ is a cyclic alkyl group in which the alkyl group is hexyl; and R² is a cyclic alkyl group in which the alkyl group is hexyl.

Claim 9 (Previously Presented): A diazodisulfone compound of the formula:



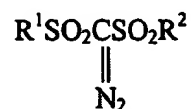
wherein R¹ is a branched alkyl group in which the alkyl group is butyl; and R² is a branched alkyl group in which the alkyl group is butyl.

Claim 10 (Previously Presented): A diazodisulfone compound of the formula:



wherein R¹ is cyclohexyl; and R² is cyclohexyl.

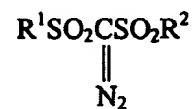
Claim 11 (Previously Presented): A diazodisulfone compound of the formula:



wherein R¹ is a branched butyl; and R² is a branched butyl.

Claim 12 (Currently Amended): A reduced light exposure energy photosensitive resist compound-material comprising:

~~an effective amount of a diazodisulfone compound of formula (I):~~



R^1 and R^2 being independently branched or cyclic alkyl groups having 3 to 8 carbon atoms, and the resist material being used for a light source of 300 nm or less at a reduced light exposure energy amount to generate an acid to create a positive tone pattern on a surface and

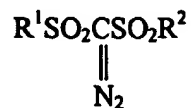
~~a polymer which is difficultly soluble in an alkaline developing solution but which can become alkali-soluble by the action of an acid,~~

wherein ~~the effective amount of~~ the resist compound is used for a light source of 300 nm or less at a reduced light exposure energy amount to generate an acid to create a positive tone pattern on a surface having a polymer, which is difficultly soluble in an alkaline developing solution but which can become soluble by the action of an acid, and the resist diazodisulfene compound is sufficient for the polymer on an ~~in the~~ exposed portion to become alkali-soluble by a chemical change with the acid generated from the resist diazodisulfene compound by light exposure energy.

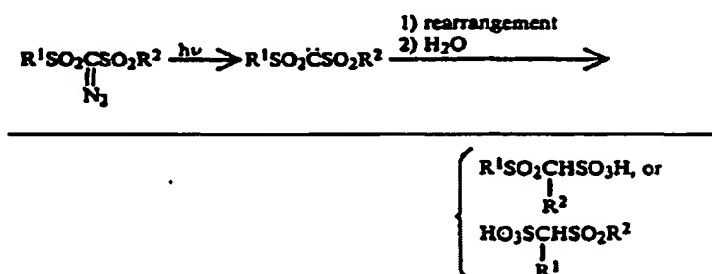
Claim 13 (Currently Amended): The photosensitive resist compound material of claim 12, wherein the light source ~~sources~~ is selected from the group consisting of deep UV light and KrF excimer laser light (248.4 nm).

Claim 14 (Currently Amended): A reduced light exposure energy photosensitive resist compound material comprising:

~~an effective amount of a diazodisulfene compound of formula (I):~~

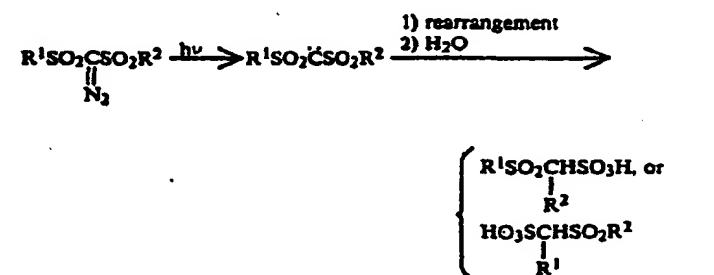


R^1 and R^2 being independently branched or cyclic alkyl groups having 3 to 8 carbon atoms, and the compound of formula (I), which when exposed to KrF eximer light generates an acid by the following reaction scheme:



and,

a polymer which is difficultly soluble in an alkaline developing solution but which can become alkali soluble by the action of an acid; wherein the photosensitive resist compound, when exposed to KrF eximer light, generates an acid by the following reaction scheme:



Claim 34 (New): The diazodisulfone compound of claim 8, wherein the resist compound is used for a light source of 300 nm or less at a reduced light exposure energy amount to generate an acid to create a positive tone pattern on a surface having a polymer, which is difficultly soluble in an alkaline developing solution but which can become soluble by the action of an acid, and the resist compound is sufficient for the polymer on an exposed portion to become alkali-soluble by a chemical change with the acid generated from the resist compound by light exposure energy.

Claim 35 (New): The diazodisulfone compound of claim 9, wherein the resist compound is used for a light source of 300 nm or less at a reduced light exposure energy amount to generate an acid to create a positive tone pattern on a surface having a polymer, which is difficultly soluble in an alkaline developing solution but which can become soluble by the action of an acid, and the resist compound is sufficient for the polymer on an exposed portion to become alkali-soluble by a chemical change with the acid generated from the resist compound by light exposure energy.